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APPLICATION NO.	FILING DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.
10/801,798	03/17/2004	Kyoko Izuha	04329.3271	1896
22852	7590 06/08/2006		EXAMINER	
FINNEGAN, HENDERSON, FARABOW, GARRETT & DUNNER			WHITMORE, STACY	
LLP 901 NEW YORK AVENUE, NW			ART UNIT	PAPER NUMBER
WASHINGTON, DC 20001-4413			2825	
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Please find below and/or attached an Office communication concerning this application or proceeding.

DETAILED ACTION

1. Applicant's election without traverse of Group I, claims 1, 3, 5, 7, 9, 11, 13, and 15 in the reply filed on May 11, 2006 is acknowledged.

Claim Objections

2. Claim 3 is objected to because of the following informalities: The claim term "Foulier" is an apparently misspelled word. The word should be "Fourier". Appropriate correction is required.

Claim Rejections - 35 USC § 112

The following is a quotation of the second paragraph of 35 U.S.C. 112: The specification shall conclude with one or more claims particularly pointing out and distinctly claiming the subject matter which the applicant regards as his invention.

- 3. Claims 1, 3, 7, 9, 11, 13, and 15 are rejected under 35 U.S.C. 112, second paragraph, as being indefinite for failing to particularly point out and distinctly claim the subject matter which applicant regards as the invention.
- In claims 1 and 15, lines 3-4, the limitation "which is predicted from a design pattern" is unclear. It is unclear which pattern is being referred to, the desired or the finish pattern. Applicant is requested to clarify the claim language.

Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

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(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

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- 4. Claims 1, 11, 13, and 15 are rejected under 35 U.S.C. 102(b) as being anticipated by Chang (US Patent 6,470,489).
- 5. As for the claims, Chang discloses the invention as claimed, including:

An edge deviation calculation method in which a desired pattern is compared with a finish pattern to be formed on a wafer, which is predicted from a design pattern, based on a calculation of a light beam intensity, and a deviation quantity of the finish pattern from the desired pattern at each of edges of the finish pattern and the desired pattern is calculated, the calculation method comprising:

setting a reference light beam intensity for setting the desired pattern on a wafer [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

setting an evaluation point for the finish pattern with the desired comparison of pattern [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

calculating a light beam intensity at the evaluation point [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

calculating a differentiation value of the light beam intensity at the evaluation point [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

calculating an intersection of the differentiation value with the reference light beam intensity [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27]; and

calculating a difference between the intersection and the evaluation point [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

wherein the difference is defined as an edge deviation quantity of the finish pattern from the desired pattern [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

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changing at least one of the reference light beam intensity and focus within each of determined ranges, and comparing the mask pattern with the finish pattern [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

wherein the design pattern is a corrected pattern corrected to provide the desired pattern [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

verifying the edge deviation quantity [abstract; figs. 12, 21-23; and col. 4 – col. 5, line 27];

wherein, in the case where the edge deviation quantity exceeds an allowable range, the design pattern is corrected based on the deviation quantity [abstract; figs. 12, 21-23; and col. 4 - col. 5, line 27].

Allowable Subject Matter

- 6. Claims 3, 5, 7, and 9 would be allowable if rewritten to overcome the rejection(s) under 35 U.S.C. 112, 2nd paragraph, set forth in this Office action and to include all of the limitations of the base claim and any intervening claims.
- 7. The following is a statement of reasons for the indication of allowable subject matter: The prior art of record fails to disclose either singularly or in combination the invention as claimed, including the method of edge deviation calculation comprising at least the calculating steps of claim 3; the calculating step of claim 5; the n-story differentiation of a light beam intensity comprising the polynomial of claim 7; and the n-story differentiation of a light beam intensity comprising the polynomial and Taylor expansion of claim 9.
- 8. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Stacy A. Whitmore whose telephone number is (571) 272-1685. The examiner can normally be reached on Monday-Thursday, alternate Friday 6:30am 4:00 pm.

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If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Jack Chiang can be reached on (571) 272-7483. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

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Stacy A Whitmore Primary Examiner Page 5

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SAW

May 27, 2006